Program at a Glance

Tuesday - May 26th

| 8:00 AM - 3:00 PM | Short Course: State of the Art Nanofabrication - Fundamentals and Applications |
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| 3:00 PM - 6:00 PM | Commercial Session |
| 6:30 PM - 9:00 PM | Welcome Reception |

Wednesday - May 27th

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| 8:00 AM - 8:15 AM | Plenary | Wele | come |
| 8:15 AM - 8:55 AM | | Julia Greer, Caltech | |
| 8:55 AM - 9:35 AM | | Kevin Gunderson, Illumina | |
| 9:35 AM - 10:15 AM | | Lynn Rothschild, NASA | |
| 10:15 AM - 10:30 AM | Break (exhibits open) | | |
| 10:30 AM - 12:00 PM | Poster Session Part 1 - Best Poster Competition | | |
| 12:00 PM - 1:15 PM | Women in Nanofabrication Lunch, lunch on your own (exhibits open) | | |
| 1:15 PM - 3:15 PM | Session 1A - Directed Self Assembly 1 | Session 1B - Nano- and Micro- Electromechanical Systems | Session 1C - Beam Induced Deposition and Etching 1 |
| 3:15 PM - 3:30 PM | Break (exhibits open) | | |
| 3:30 PM - 5:25 PM | Session 2A - Nanoimprint Lithography 1 | Session 2B - Nanophotonics 1 | Session 2C - Focused Ion Beam Technology 1 |
| 5:25 PM - 5:35 PM | Break | | |
| 5:35 PM - 7:00 PM | Poster Session Part 2 | | |
| Thursday - May 28 th | | | |
| 8:00 AM - 10:00 AM | Session 3A - Nanobiotechnology 1 | Session 3B - Advanced Pattern Transfer | Session 3C - Beam Induced Depo- sition and Etching 2 |
| 10.00 AM - 10.15 AM | Prock (avhibits apon) | | |

| 10:00 AM - 10:15 AM | Break (exhibits open) | | | |
|---------------------|--|--|---|--|
| 10:15 AM - 12:15 PM | Session 4A - Plasmonics | Session 4B - Nanostructures for Quantum Computing | Session 4C - Electron Beam Lithography 1 | |
| 12:15 PM - 1:30 PM | Lunch on your own (exhibits open) | | | |
| 1:30 PM - 3:30 PM | Session 5A - Optical and Extreme UV (EUV) Lithography | Session 5B - Atomic Layer Deposition | Session 5C - Beam Induced Depo- sition and Etching 3 | |
| 3:30 PM - 3:45 PM | Break | | | |
| 3:45 PM - 5:35 PM | Session 6A - Nanoimprint Lithography 2 | Session 6B - Nanoelectronics 1 | Session 6C - Electron Beam Lithography 2 | |
| 6:00 PM - 9:00 PM | | EIPBN Banquet | | |

Friday - May 29th

| 8:00 AM - 9:50 AM | Session 7A - | Session 7B - | Session 7C - | |
|---------------------|-----------------------------------|-------------------------------|--------------------------------|--|
| | Nanophotonics 2 | Nanoelectronics 2 | Focused Ion Beam Technology 2 | |
| 9:50 AM - 10:05 AM | Break | | | |
| 10:05 AM - 12:05 PM | Session 8A - | Session 8B - Special Session: | Session 8C - Charged Particle | |
| | Resists and Lithography Materials | Nanoscience User Facilities | Optics and Sources | |
| 12:05 PM - 1:20 PM | Lunch on your own | | | |
| 1:20 PM - 3:20 PM | Session 9A - | Session 9B - | Session 9C - Novel Imaging and | |
| | Nanobiotechnology 2 | Emerging Technologies | Characterization Techniques | |
| 3:20 PM - 3:35 PM | Break | | | |
| 3:35 PM - 5:25 PM | Session 10A - | Session 10B - | Session 10C - High Throughput | |
| | Directed Self Assembly 2 | Micro- and Nanofluidics | Electron Microscopy | |